POLISHING LIQUID, METHOD FOR MANUFACTURING GLASS SUBSTRATE, AND METHOD FOR MANUFACTURING MAGNETIC DISK

ABSTRACT

Letting a particle diameter be Dx [μm] when a cumulative particle volume cumulated from the small particle diameter side reaches x[%] of the total particle volume in a particle size distribution obtained regarding cerium oxide included in a polishing liquid using a laser diffraction/scattering method, D5 is 1 μm or less, and a difference between D95 and D5 is 3 μm or more.

[FIG. 1]